ABSTRACT

The invention is directed to a microprocessing treatment agent for use in fine processing of an object having a silicon nitride film and a silicon oxide film, which includes: at least one of a component (A) or a component (B); a component (C); and a component (D), wherein the component (A) is 0.01-20% by weight of hydrogen fluoride, the component (B) is 0.1-20% by weight of at least one of ammonium fluoride or quaternary ammonium fluoride, the component (C) is 1-80% by weight of at least one acid selected from the group consisting of hydrochloric acid, nitric acid, sulfuric acid, and phosphoric acid, the component (D) is water, and the total content of at least one of the component (A) or the component (B) and the component (C) is 90% by weight or less, based on the total amount of the microprocessing treatment agent.